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(54) Title of the Invention:

Method of forming contact window

**Abstract:**

The present invention relates to a method of forming a metal window, which involves forming a first metal layer 13 on a semiconductor substrate 11 so that the first metal layer 13 can be electrically connected to a predetermined active region on the semiconductor substrate 11. In particular, the method involves forming a photosensitive layer pattern 14 on a region where a contact window will be placed, forming an interlayer dielectric layer 15 on the semiconductor substrate 11 so that the upper surface of the photosensitive layer pattern 14 can be exposed, and removing the photosensitive layer pattern 14. Accordingly, it is possible to form fine patterns and lower contact resistance.